

Notice of References Cited		Application/Control No.	Applicant(s)/Patent Under Reexamination	
		10/790,492	ZHENG ET AL.	
Examiner Toniae M. Thomas		Art Unit 2822	Page 1 of 1	

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-			
	B	US-			
	C	US-			
	D	US-			
	E	US-			
	F	US-			
	G	US-			
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FOREIGN PATENT DOCUMENTS

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	N					
	O					
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	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
*	U	Hausemann et al., "Rapid Vapor Deposition of Highly Conformal Silica Nanolaminates," Science, Vol. 298, October 11, 2002, pages 402-406.
	V	
	W	
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.